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### **PCT**

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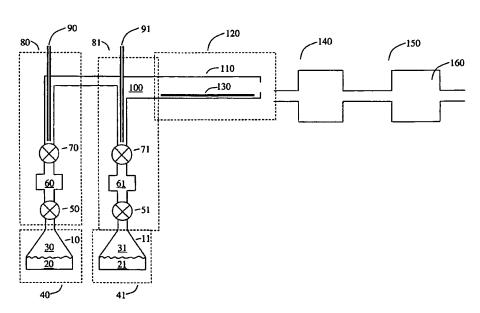
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(88) Date of publication of the international search report:

10 October 2002

For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.

(54) Title: VAPOR DEPOSITION OF OXIDES, SILICATES AND PHOSPHATES



(57) Abstract: Metal silicates or phosphates are deposited on a heated substrate by the reaction of vapors of alkoxysilanols or alkylphosphates along with reactive metal amides, alkyls or alkoxides. For example, vapors of tris-(ter-butoxy)silanol react with vapors of tetrakis(ethylmethylamido)hafnium to deposit hafnium silicate on surfaces heated to 300 °C. The product film has a very uniform stoichiometry throughout the reactor. Similarly, vapors of diisopropylphosphate react with vapors of lithium bis(ethyldimethylsilyl)amide to deposit lithium phosphate films on substrates heated to 250 °C. supplying the vapors in alternating pulse produces these same compositions with a very uniform distribution of thickness and excellent step coverage.

02/027063 A3





# A. CLASSIFICATION OF SUBJECT MATTER IPC 7 C23C16/40 C23C16/44

C. DOCUMENTS CONSIDERED TO BE RELEVANT

According to international Patent Classification (IPC) or to both national classification and IPC

### B. FIELDS SEARCHED

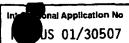
Minimum documentation searched (classification system followed by classification symbols) IPC 7 C23C

Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched

Electronic data base consulted during the international search (name of data base and, where practical, search terms used)

PAJ, WPI Data, EPO-Internal, INSPEC, IBM-TDB, COMPENDEX

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X Furti	her documents are listed in the continuation of box C.	X Patent family members are listed to	n annex.		
Special categories of cited documents:      A document defining the general state of the art which is not considered to be of particular relevance.		"T" later document published after the International filing date or priority date and not in conflict with the application but cited to understand the principle or theory underlying the invention			
filing d  "L" docume which citation "O" docume other r	ent which may throw doubts on priority claim(s) or is cited to establish the publication date of another n or other special reason (as specified) ent referring to an oral disclosure, use, exhibition or means	<ul> <li>"X" document of particular relevance; the cl cannot be considered novel or cannot involve an inventive step when the doc</li> <li>"Y" document of particular relevance; the cl cannot be considered to involve an inv document is combined with one or mo ments, such combination being obviou in the art.</li> </ul>	be considered to current is taken alone aimed Invention entive step when the re other such docu—		
*P* document published prior to the international filling date but later than the priority date claimed		'&' document member of the same patent family			
Date of the	actual completion of the international search	Date of mailing of the international sea	rch report		
9	August 2002	1 9. 08. 02			
Name and r	nailing address of the ISA European Patent Office, P.B. 5818 Patentlaan 2 NL – 2260 HV Rijswijk Tel. (+31–70) 340–2040, Tx. 31 651 epo nl, Fax: (+31–70) 340–3016	Authorized officer  Ekhult, H			



	W. A COMMENTAL CONTROL TO DE DEL EVALUE	
Category *	ation) DOCUMENTS CONSIDERED TO BE RELEVANT  Citation of document, with Indication, where appropriate, of the relevant passages	Relevant to claim No.
Calegory	Challen of document, with meadown, more appropriate, or all the second representations.	
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X	WO 97 38355 A (MICRION CORP) 16 October 1997 (1997-10-16) page 3, line 4 - line 9	22
X	WO 99 29924 A (NESTE OYJ ;SUNTOLA TUOMO (FI); LESKELAE MARKKU (FI); RITALA MIKKO) 17 June 1999 (1999-06-17)	28
Y	page 5, line 4 - line 13	29,30
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International application No. PCT/US 01/30507

Box I	Observations where certain claims were found unsearchable (Continuation of Item 1 of first sheet)
This Inte	mational Search Report has not been established in respect of certain claims under Article 17(2)(a) for the following reasons:
1.	Claims Nos.: because they relate to subject matter not required to be searched by this Authority, namely:
2.	Claims Nos.: because they relate to parts of the International Application that do not comply with the prescribed requirements to such an extent that no meaningful International Search can be carried out, specifically:
з. 🔲	Claims Nos.: because they are dependent claims and are not drafted in accordance with the second and third sentences of Rule 6.4(a).
Box II	Observations where unity of invention is lacking (Continuation of item 2 of first sheet)
This Inte	mational Searching Authority found multiple inventions in this international application, as follows:
	see additional sheet
1.	As all required additional search fees were timely paid by the applicant, this international Search Report covers all searchable claims.
2.	As all searchable claims could be searched without effort justifying an additional fee, this Authority did not invite payment of any additional fee.
з. 🗶	As only some of the required additional search fees were timely paid by the applicant, this International Search Report covers only those claims for which fees were paid, specifically claims Nos.:  1-11,22-24,28-30
4.	No required additional search fees were timely paid by the applicant. Consequently, this International Search Report is restricted to the invention first mentioned in the claims; it is covered by claims Nos.:
Remark	The additional search fees were accompanied by the applicant's protest.   No protest accompanied the payment of additional search fees.

### FURTHER INFORMATION CONTINUED FROM PCT/ISA/ 210

This International Searching Authority found multiple (groups of) inventions in this international application, as follows:

1. Claims: 1-11,22-24

CVD process using alkoxysilan(di)ol.

2. Claims: 12-21,25

CVD process using bis(alkyl)phosphates.

3. Claims: 26,27,31,32

CVD process using arene hydrates.

4. Claims: 28-30

CVD process using amides and alcohol or water.

nformation on patent family members

In Snal Application No US 01/30507

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